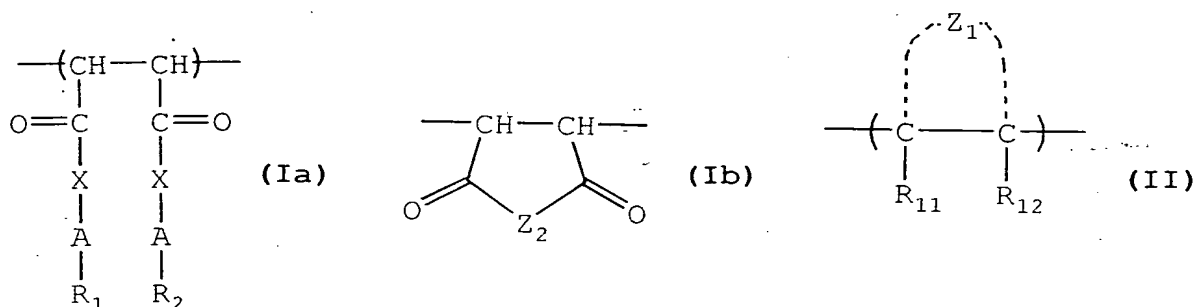


ABSTRACT OF THE DISCLOSURE

The present invention provides a positive photoresist composition for far ultraviolet exposure, which comprises a polymer having at least one of a repeating unit represented by formula (Ia) and a repeating unit represented by formula (Ib), and a repeating unit represented by formula (II), and having a group capable of decomposing by the action of an acid:



wherein R_1 and R_2 each represents hydrogen atom, a cyano group, a hydroxyl group, -COOH , -COOR_5 , -CO-NH-R_6 , $\text{-CO-NH-SO}_2\text{-R}_6$, an alkyl group, an alkoxy group, a cyclic hydrocarbon group or a -Y group, X represents -O- , -S- , -NH- , $\text{-NHSO}_2\text{-}$ or $\text{-NHSO}_2\text{NH-}$, A represents a single bond or a divalent linking group, Z_2 represents -O- or $\text{-N(R}_3\text{)-}$, R_{11} and R_{12} each represents a hydrogen atom, a cyano group, a halogen atom or an alkyl group, Z_1 represents an atomic group necessary for forming an alicyclic structure which contains two bonded carbon atoms (C-C), and Y , R_3 , R_5 and R_6 are as defined in the specification.